# Flat and Cross-Sectional Milling with the New Hitachi IM4000II Ion Mill

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# Ion Milling What is it?



- Ion milling: a general term for sample preparation methods that involve removing sample material by bombarding the surface with ions, in a process called sputtering.
- An ion mill typically refers to instruments that use a broad beam of Argon ions to gently smooth sample surfaces with minimal defects or artifacts compared to other techniques. Broad Ion Beam (BIB)



### Hitachi IM4000II







Img: Japan Atomic Energy Research Institute













Newbury and Ritchie 2012







Oxford Instruments

### **EBSD Pattern Quality vs Surface Quality**

Nowell et al. 2005









Oxford Instruments

### EBSD Pattern Quality vs Surface Quality



Hitachi High Tech



Northwestern EXPLORING INNER SPACE













Razor blade

Ion Mill

Hitachi High Tech









Cleaved



Ion Mill



#### https://www.latticegear.com

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#### **Cutting/Slicing**

#### Cleaving

#### Grinding / Polishing

#### Microtomy

Focused Ion Beam (FIB)

Broad Ion Beam (BIB)





Hitachi High Tech







#### Microscopy Australia, Myscope.Training













#### Focused Ion Beam (FIB)



Helios 5 Hydra CX PFIB

#### Fischione 1040 NanoMill



#### Broad Ion Beam (BIB)



Hitachi IM4000II



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Focused Ion Beam (FIB)







Focused Ion Beam (FIB)



Spot sizes	nm-regime, converged beam	mm regime, broad, near parallel beam.
Current	lower current/ higher current density	higher current, lower current density
Acc. Voltage	Usually 30kV, lower for cleaning	Usually < 10kV





#### Focused Ion Beam (FIB)

- High site specificity
- Relatively slow milling rates
- Implantation damage, amorphization
  - low kV clean up important! (Nanomill)
- Usually Ga, also Xe, O, N, and Ar options and more.
- Great for:
  - TEM liftouts
  - Atom probe prep
  - nanomachining,
  - 3D tomography/EBSD
  - $\circ~$  Cross-sections (tens of  $\mu m^2$ , site specific)

#### Broad Ion Beam (BIB)

- Low site specificity.
- Relatively fast milling rates,
- Minimal damage
- Usually Ar ions, others less common.
- Great for:
  - Polishing for EDS/WDS/EBSD
  - Damage/contamination removal
  - Cross-sections (~10-20 mm<sup>2</sup>)





## Hybrid Milling in the Hitachi IM4000II







#### Hitachi High Tech



- ± 30 degree swing angle
- 500  $\mu$ m/h or greater
- 20(W) × 12(D) × 7(H) mm

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### **Cross Sections**

#### Focused Ion Beam (FIB)

#### Broad Ion Beam (BIB)





Desbois et al 2010

## Notice the scale!





# Hybrid Milling in the Hitachi IM4000II









# Flat Milling

Hitachi High Tech





- 50 (W) x 25 (H) specimens
- 32 mm max diameter











# Flat/Relief Milling



θ -3400N 5.00kV x4.00k BSECOMP 40Pa 10.0un θ 10.0um S-3400N 5.00kV x4.00k BSECOMP 40Pa

Northwestern University Atomic and Nanoscale Characterization Experimental Center

Hitachi High Tech



## Additional capabilities







# Thank you!



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Register for Ion Mill Training!



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